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(21)Application number : 07-285790 (71)Applicant : HITACHI CHEM CO LTD

(22)Date of filing : 02.11.1995 (72)Inventor : TANAKA HIROYUKI
TACHIKI HIDEYASU
NOJIRI TAKESHI
UEJIMA KOICHI
TAI SEIJI
TANNO SEIKICHI
KAKUMARU HAJIME

(54) PHOTOSENSITIVE RESIN COMPOSITION AND PRODUCTION OF
PHOTORESISTIVE FILM AND FLUORESCENT PATTERN USING SAME

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain a resin compsn. not increasing its viscosity over a long period of time and excellent in shelf stability by incorporating a specified phosphor, a specified resin, a photopolymerizable unsatd. compd. and a photo- initiator.

SOLUTION: This resin compsn. contains a phosphor (A) surface-treated with a compd. having a carboxyl group, a resin (B) having carboxyl groups, a photopolymerizable unsatd. compd. (C) having an ethylenically unsatd. group and a photo-initiator (D) generating free radicals when irradiated with active light. The phosphor A is obtd. usually by surface-treating a metal oxide-base phosphor with a compd. having a carboxyl group. The resin B is obtd. by copolymerizing unsatd. carboxylic acid with one or more kinds of other unsatd. monomers each copolymerizable with the carboxylic acid. Any known photopolymerizable monofunctional monomer may be used as the unsatd. compd. C.

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